



1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Number: 09/885,792

Filing Date: 06/20/2001

Applicant: Basanth Jagannathan

5 Application Title: **A NON-SELF-ALIGNED SiGe
HETEROJUNCTION BIPOLAR
TRANSISTOR**

Examiner: Latin, Christopher W.

Art Unit: 2812

10 **DECLARATION UNDER 37 CFR 1.131**

Commissioner of Patents
P.O. BOX 1450
Alexandria, VA 22313-1450
Sir:

15

Basant Jagannathan, Shwu-Jen Jeng, Jeffrey B. Johnson, Robb A. Johnson, Louis D. Lanzerotti, Kenneth J. Stein, and Seshadri Subbanna, applicants in the above-identified patent application, declare as follows:

20 1) During a period of time prior to September 1, 2000, the 35 USC 102(e) date of US patent 6,410,975 to Racanelli, we worked as a team and conceived of and reduced to practice the invention disclosed and claimed in the above-referenced application.

25 2) Specific proof of our conception and reduction to practice is evidenced by the attached Exhibit A (Disclosure FIS8-2000-0337), which is a confidential invention disclosure form used within the assignee corporation, IBM. The exhibit was prepared in preparation of a patent application. The work associated with the attached exhibit was the basis for the patent application referenced above.

30 3) Exhibit A describes and illustrates the non-self aligned transistor and fabrication method of the present invention. Specifically, Figs. 1a-1j of Exhibit A illustrate the prior art (also illustrated in Figs. 1A-1J in the present specification). Figs. 2a-2i of Exhibit A

illustrate the method of the present invention, including steps of intrinsic base implant (Fig. 2g) and deposition of the nitride layer (Fig. 2d) that provides an implant mask over the emitter pedestal.

5 4) The discussion on page 6 of Exhibit A provides further evidence of conception and reduction to practice.

5) Exhibit A was last modified on June 27, 2000 (see the top of page 1). This Exhibit demonstrates both conception and reduction to practice of the invention prior to the filing
10 date of the Racanelli reference (September 1, 2000).

6) We further declare that all statements made herein of our own knowledge are true and that all statements made on information and belief are believed to be true, and further, that these statements were made with the knowledge that willful, false statements so
15 made are punishable by fine or imprisonment, or both, under section 1001 of Title 18 of the United States Code, and that such willful, false statements may jeopardize the validity of the above-referenced application and any patent issuing thereon.

20 Date _____ Basanth Jagannathan _____

Date _____ Shwu-Jen Jeng _____

Date 9/3/03 Jeffrey B. Johnson Jeff B. Johnson

25 Date _____ Robb A. Johnson _____

Date 9/3/03 Louis D. Lanzetta _____

Date _____ Kenneth J. Stein _____

30

Date _____ Seshadri Subbanna, _____

EXHIBIT A

**Disclosure FIS8-2000-0337**

Created By: Shwu-Jen Jeng Created On: 09/07/99 02:14:47 PM

Last Modified By: Hilda Heinlein Last Modified On: 06/27/2000 05:19:53 PM

*** IBM Confidential ***

Required fields are marked with the asterisk (*) and must be filled in to complete the form.

Summary

Status	Under Evaluation
Processing Location	FIS
Functional Area	ZZISA-Issac
Attorney/Patent Professional	Joseph Abate/Fishkill/IBM
IDT Team	Michael Hargrove/Fishkill/IBM; William Davine/Fishkill/IBM; Jack Mandelman/Fishkill/IBM; Louis Hsu/Fishkill/IBM; Peter Smeys/Fishkill/IBM; DOMINIC SCHEPIS/Fishkill/IBM; Patricia A O'Neil/Fishkill/IBM
Submitted Date	08/27/2000 09:30:20 AM
Owning Division	MD
PVT Score	To calculate a PVT score, use the 'Calculate PVT' button.
Incentive Program	
Lab	
Technology Code	101N5

Inventors with Lotus Notes IDs

Inventors: Shwu-Jen Jeng/Fishkill/IBM, Sasanth Jagannathan/Fishkill/IBM, Kenneth Stein/Fishkill/IBM, Seshadri Subbanna/Fishkill/IBM, Robb Johnson/Burlington/IBM, Jeffrey Johnson/Burlington/IBM@IBMUS, Louis Lanzerotti/Burlington/IBM

Inventor Name > denotes primary contact	Inventor Serial	Div/Dept	Manager Serial	Manager Name
Jeng, Shwu-Jen	292585	29/U7A	403838	Almgren, David C.
Jagannathan, Sasanth	545895	29/U7FA	403838	Almgren, David C.
Stein, Kenneth J.	154888	29/U7TA	403838	Almgren, David C.
Subbanna, Seshadri	445835	29/SDEA	193247	Herman, Dean A.
Johnson, Robb A.	805238	29/ATUV	581979	Dunn, J.S. (Jim)
Johnson, J.B. (Jeffrey)	433840	29/AJEA	048408	Hargrave, David L.
Lanzerotti, Louis D.	953904	29/ETAA	885238	Johnson, Robb A.

Inventors without Lotus Notes IDs**IDT Selection**

IDT Team	Attorney/Patent Professional
Michael Hargrove/Fishkill/IBM	Joseph Abate/Fishkill/IBM
William Davine/Fishkill/IBM	
Jack Mandelman/Fishkill/IBM	
Louis Hsu/Fishkill/IBM	
Peter Smeys/Fishkill/IBM	
DOMINIC SCHEPIS/Fishkill/IBM	
PATRICIA O'NEIL/Fishkill/IBM	

FISB-2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) - continued

Response Due to P&C: 07/27/2000

Main Idea**Title of disclosure (in English)****A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT)****Idea of disclosure**

1. Describe your invention, stating the problem solved (if appropriate), and indicating the advantages of using the invention.

Using a non-self aligned scheme to replace the emitter pedestal and self-aligned extrinsic base structure, the total process time and thermal cycle for the non-self aligned scheme will be reduced compared to the self-aligned structure. In the simplified process of forming the non-self aligned emitter, due to the reduced transient enhanced diffusion of the dopants much sharper and narrower doping profiles can be obtained. As a result, the transistor structure can be tailored for high-speed performance. The reduced process time also lowers the cost of fabricating the device.

A related advantage in this low thermal cycle processing is that it allows for making use of thin LTE layers to form base and collector regions. This leads to possibilities of even higher speed devices. The ability to integrate thin LTE layers in this structure also implies that the overall device topography can be lowered making MEOL processing much easier.

2. How does the invention solve the problem or achieve an advantage, (a description of "the invention", including figures inline as appropriate)?

After LTE in-situ boron doped base been put down, a conventional dielectric emitter pedestal and a self-aligned extrinsic base spacer structure as shown in Figure 1j will require additional pedestal RIE, spacer deposition and etch, oxide strip, high pressure oxidation, and emitter opening RIE process steps before reaching emitter poly deposition. (The film thickness scaled down by approximately 20% from generation 5HP to generation 7HP.)

Insert text description of ETX process (5 and 6HP) for Figures 1a-1j.

- Sub-Collector
- Shallow Trench Isolation
- Reach-Through

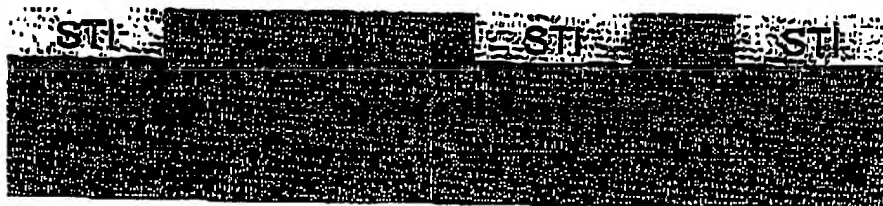


Figure 1a.

FISB-2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) - continued

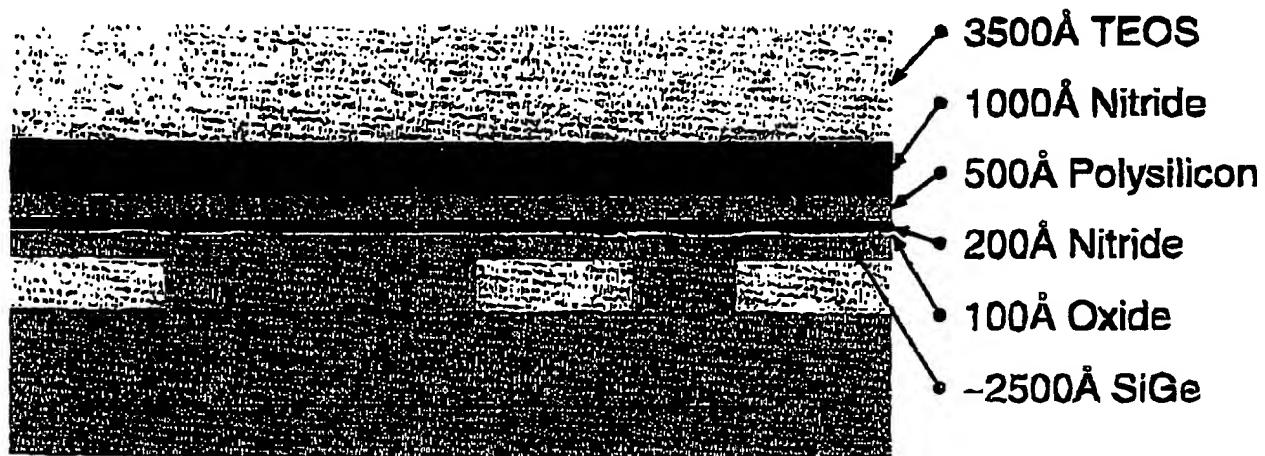


Figure 1b.

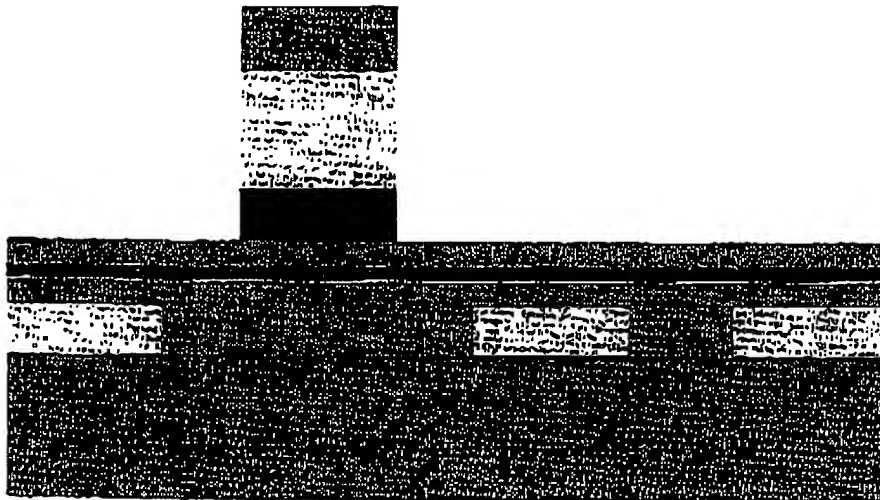


Figure 1c.

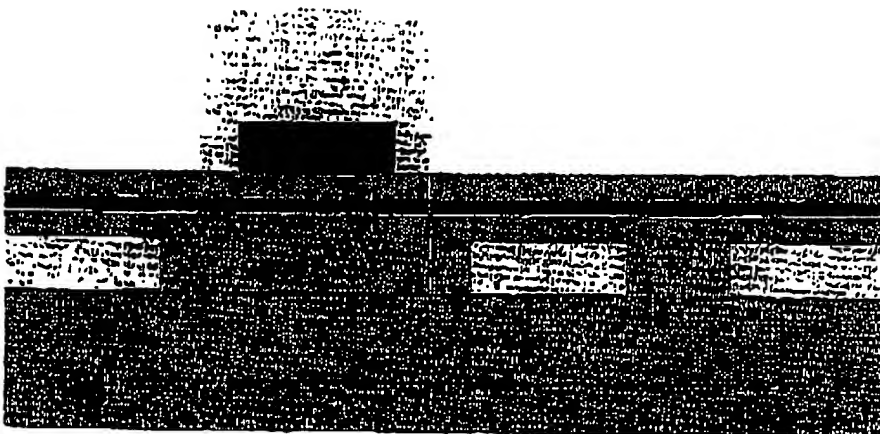


Figure 1d.

- Etch TEOS
- Etch Nitride

- Oxide Sidewall Formation
- Self-Aligned Extrinsic Base Implant
 - Boron

FIS8-2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) - continued

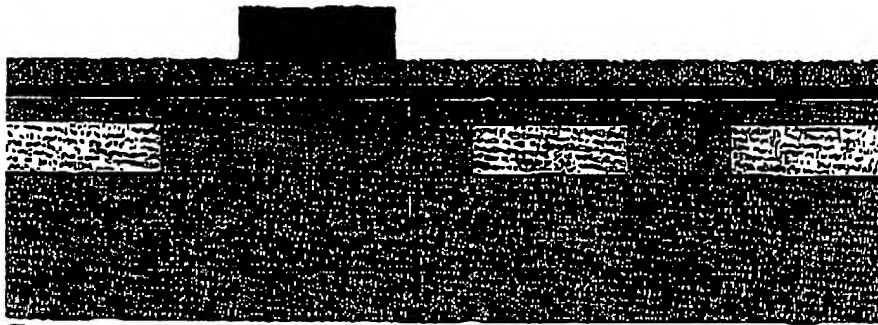


Figure 1e.

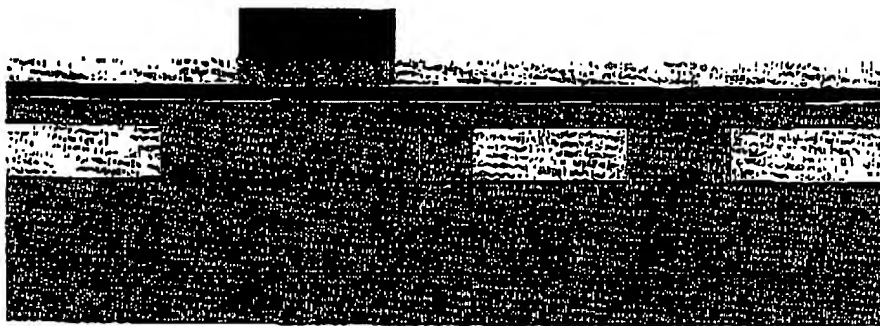


Figure 1f.

- Convert Polysilicon to Oxide
– HfPOx

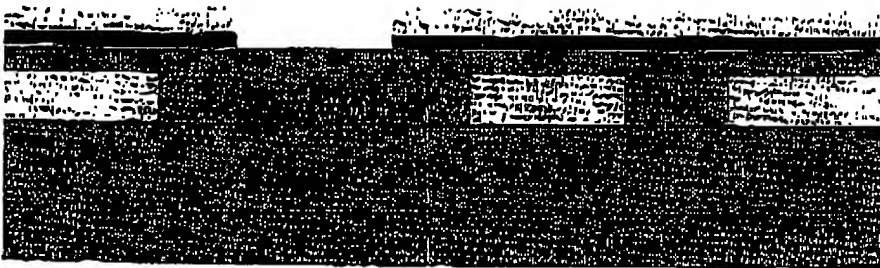


Figure 1g.

- Remove Nitride
- Remove Polysilicon
- Remove Nitride

FIGS 2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) • continued



Figure 1h.

- Pedestal Implant for High f_t Device
 - Phosphorous
- Self-aligned to Extrinsic Base Implant

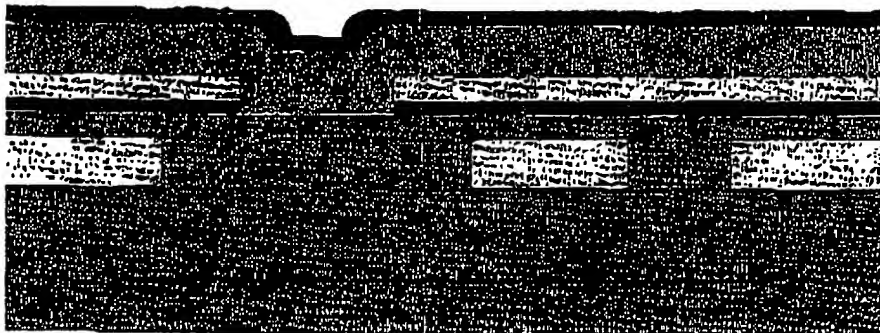


Figure 1i.

- Rapid Thermal Oxidation
- Emitter Polysilicon Deposition and Implant
 - Arsenic
- Protect Nitride
- Emitter RTA

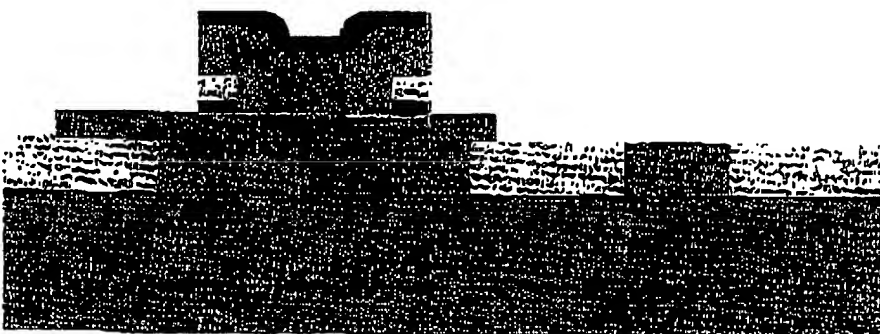


Figure 1j.

- Emitter Photo and Etch
- Base Photo and Etch

As seen from the prior art the self-aligned process is complicated and time consuming. Using a non-self aligned structure, the complicated emitter pedestal is no longer needed. Instead, the emitter stack now consists of 100Å HiPOx, 500Å RTCVD nitride, and 700Å LPVCD or PECVD TEOS as shown in Figure 2a. (The 500Å RTCVD nitride can be replaced by an 600Å PECVD nitride to further reduce thermal cycle. This 600Å PECVD nitride will

FIS8-2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) - continued

be reduced to 500Å after NP oxide strip to maintain some amount of parasitic capacitance.) Using a reverse polarity resist, the resist is developed at the emitter, and the emitter opening is defined by etching through 700Å TEOS as shown in Figure 2b. The resist is then stripped and the TEOS is then used as a hardmask to etch the 500Å nitride and stop at the 100Å HiPOx as shown in Figure 2c. Subsequently, the HiPOx is stripped (along with the hardmask), and an in-situ phosphorus doped emitter or an arsenic implanted emitter is formed as in Figure 2d. After the emitter poly is capped by nitride, the emitter is patterned and etched (Figure 2e). This is followed by patterning of the base region as in Figure 2f. Finally, the nitride-capped emitter poly is used as a mask for extrinsic base implant as shown in Figure 2g. In this case we use the PFET S/D implants for the extrinsic base doping rather than using a dedicated implant. This saves time and money. The advantage of non-self aligned structure is that no complicated emitter pedestal, spacer deposition and etch, HiPOx conversion process is required. However, the structure becomes more sensitive to alignment (relative to the self-aligned process) as shown in Figure 2h and Figure 2i. Extrinsic base resistance must be controlled by tightening the emitter poly to emitter opening photo tolerance. (LTE and emitter poly thickness will be scaled down from generation to generation.)

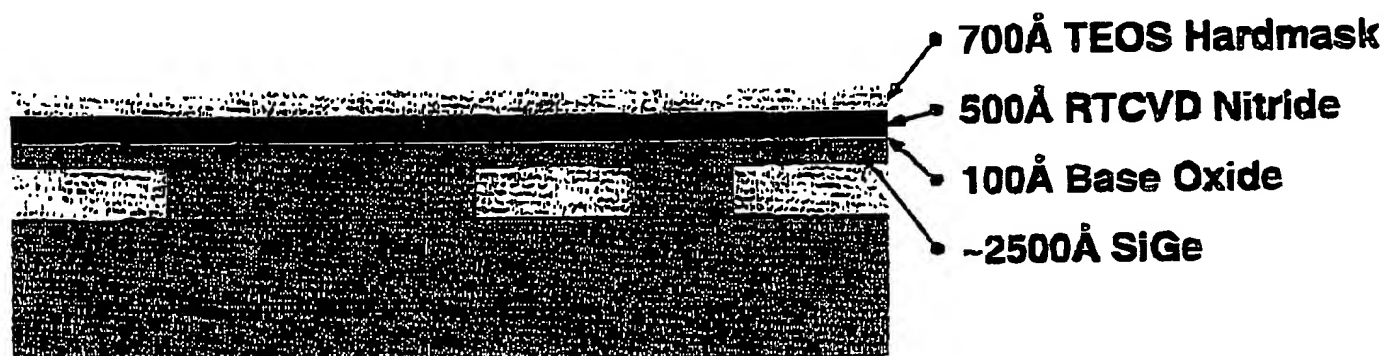


Figure 2a.

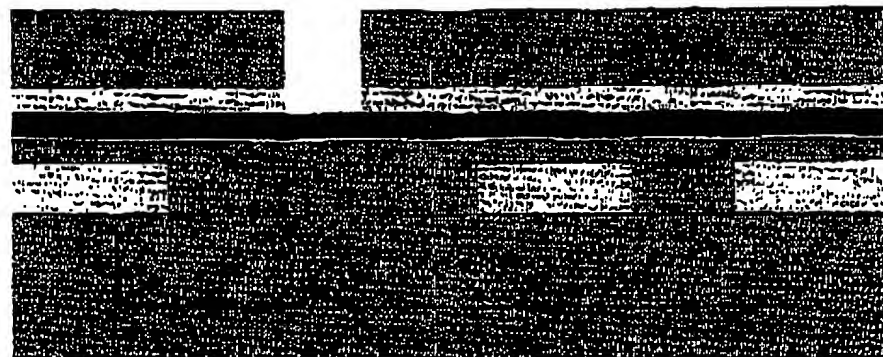


Figure 2b.

FISB-2000-0357 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) - continued

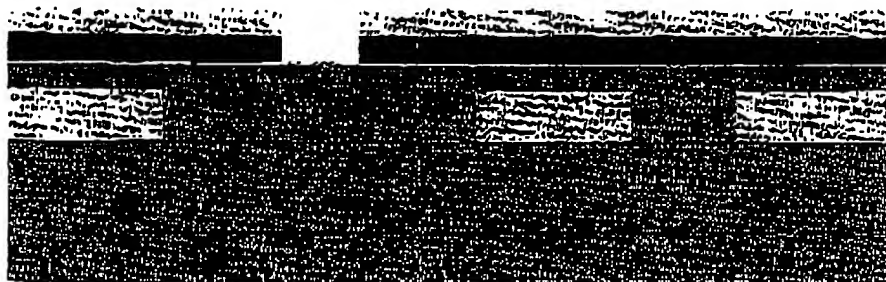


Figure 2c.

- Strip Resist
- Nitride Etch
 - Spacer chemistry
- Pedestal Implant

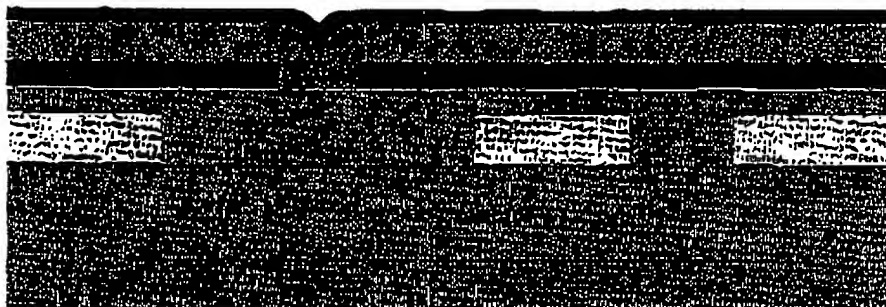


Figure 2d.

- RTO
- Emitter Polysilicon
- As⁺ Implant
- Nitride Protect

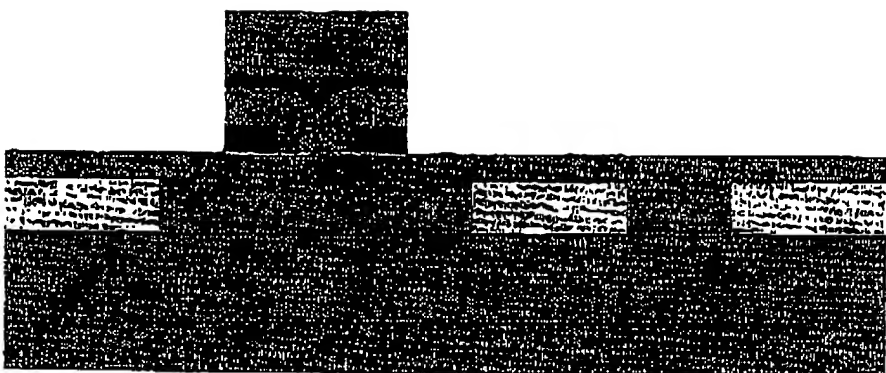
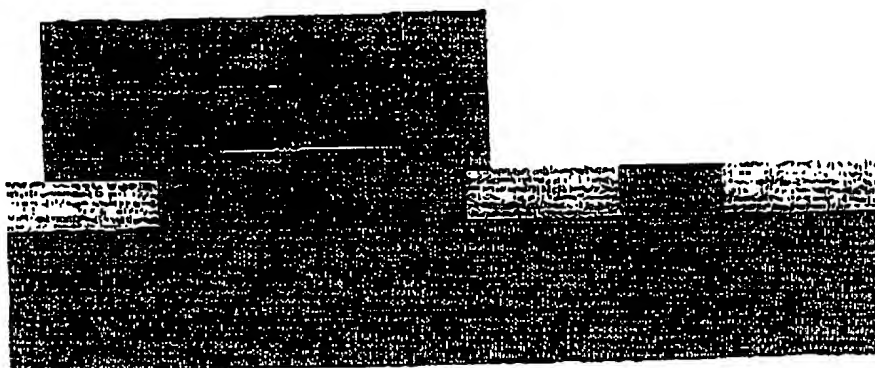


Figure 2a.

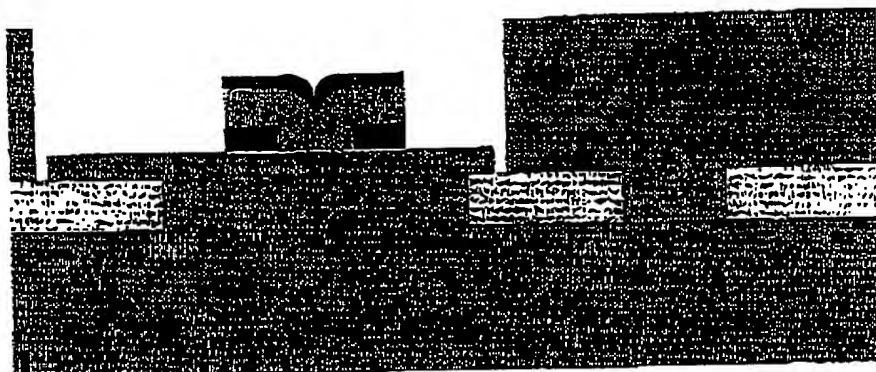
- NP Photo
- Etch Nitride
- Etch Polysilicon
- Etch Nitride

FISB-2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) • continued



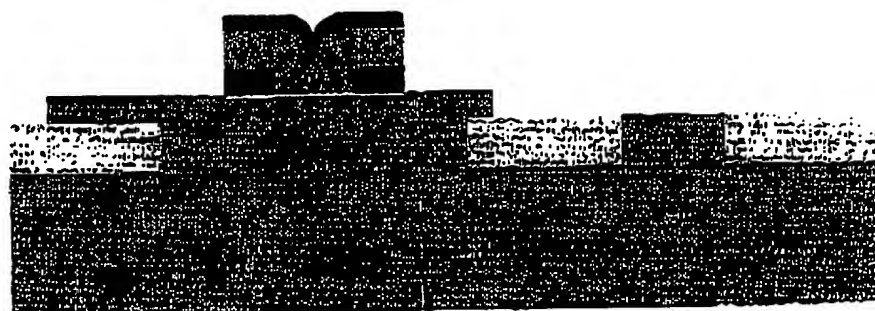
- Base Etch Stopping on STI

Figure 2f.



- BN Photo
- Extrinsic Base Implant
– FET S/D (BN)

Figure 2g.



- Perfectly aligned emitter polysilicon (NP) to emitter opening (EN) photo

Figure 2h.

FISB-2000-0337 A Non-Self Aligned SiGe Heterojunction Bipolar Transistor (HBT) - continued

• Mis-aligned NP to EN
photo

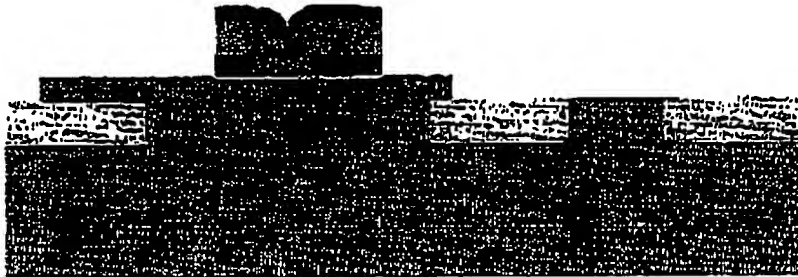


Figure 2i.

3. If the same advantage or problem has been identified by others (inside/outside IBM), how have those others solved it and does your solution differ and why is it better?

4. If the invention is implemented in a product or prototype, include technical details, purpose, disclosure details to others and the date of that implementation.

***Critical Questions (Questions 1 - 7 must be answered)**

Question 1:
On what date was the invention workable? 04/09/2000. Please format the date as MM/DD/YYYY.
Workable means i.e. when you know that your design will solve the problem.

Question 2:
Is there any planned or actual publication or disclosure of your invention to anyone outside IBM? ☐ Yes ☒ No

If yes, Enter the name of each publication or patent and the date published below:
Publication/Patent:
Date Published or Issued:

Are you aware of any publications, products or patents that relate to this invention? ☐ Yes ☒ No

If yes, Enter the name of each publication or patent and the date published below:
Publication/Patent:
Date Published or Issued:

Question 3:
Has the subject matter of the invention or a product incorporating the invention been sold, used internally in manufacturing, announced for sale, or included in a proposal? ☐ Yes ☒ No

Is a sale, use in manufacturing, product announcement, or proposal planned? ☐ Yes ☒ No

If Yes, identify the product, known and indicate the date of planned date of sale, announcement, or proposal and to whom the sale, announcement or proposal has been or will be made:
Product:
Version/Release: